Supporting Information

3D Hierarchically Mesoporous Cu-Doped NiO Hierarchical Nanostructures as

High-Performance Anodes Materials for Lithium Ion Batteries

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Figure S1. TGA and DTGA curve of β -Ni(OH)₂ precursor in air flow.



Figure S2. FESEM image of 3D hierarchical mesoporous Cu_{3%}NiO sample calcinated at 350 °C.



Figure S3. FESEM image of 3D hierarchical mesoporous Cu_{3%}NiO sample calcinated at 550 °C.



Figure S4. (a-d) SEM image and EDX element mapping of Ni, Cu, and O elements of Cu_{3%}NiO samples.



Figure S5. N₂ adsorption/desorption isotherm curve and Barrett–Joyner–Halenda (BJH) pore size distribution plot: (a, b) pure NiO, (c-f) Cu_xNiO samples with different Cu incorporated contents of 1, 3, 5%, repectively.

Sample	BET surface area	Pore diameter	Total pore
volume			
	$/m^2 g^{-1}$	/nm	/cm ³ g ⁻¹
Pure NiO	112.0	6.6	0.21
1% Cu	119.7	6.8	0.22
3% Cu	131.6	8.7	0.31
5% Cu	142.7	7.6	0.24

Table S1. Structural properties of Cu-doped sample samples annealed at 350°C.



Figure S6. Rate capability of at different current densities from 100 to 1600 mA g^{-1} in the voltage range 3.00-0.01 V versus Li⁺/Li for 60 cycles of Cu_{3%}NiO samples calcinated at temperature of 350 and 550 °C.

The electrochemical impedance spectrum (EIS) was used to investigate the charge transport kinetics for the electrochemical properties of the Cu-doped NiO samples. Nyquist plots (Figure S7) exhibit that the diameter of the semicircle for Cu/Ni=1% (annealing temperature was 350°C) in the high-medium frequency region which attributed to the ohmic resistance is much smaller than that of pure NiO sample, indicating that the porous hollow hierarchical micro/nano-material can facilitate electron transfer from doped Cu ions within the whole electrode and thus decrease resistance. The decrease of charge transfer resistance is profitable to improve the electron and ion kinetics in the composite electrode, consequently, enhancing the electrochemical performance of the Cu-doped NiO.



Figure S7. Nyquist plot of synthesized pure NiO, 1 %, 3%, and 5% Cu-doped Cu_xNiO electrodes calcinated at 350 °C.